

Sheet 1 of 1

Substitute Form PTO-1449 (Modified)	U.S. Department of Commerce Patent and Trademark Office	Attorney's Docket No. 10559-880001	Application No. 10/688,337
Information Disclosure Statement by Applicant (Use several sheets if necessary) (37 CFR §1.98(b))		Applicant Yan Borodovsky	
		Filing Date October 17, 2003	Group Art Unit 1765

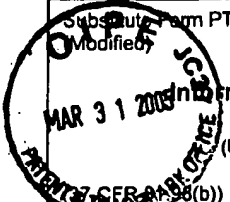
U.S. Patent Documents							
Examiner Initial	Desig. ID	Document Number	Publication Date	Patentee	Class	Subclass	Filing Date If Appropriate
	AA						
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Foreign Patent Documents or Published Foreign Patent Applications								
Examiner Initial	Desig. ID	Document Number	Publication Date	Country or Patent Office	Class	Subclass	Translation	
	AL						Yes	No
	AM							
	AN							
	AO							
	AP							

Other Documents (include Author, Title, Date, and Place of Publication)		
Examiner Initial	Desig. ID	Document
DCD	AQ	"Gratings of regular arrays and trim exposures for ultralarge scale integrated circuit phase-shift lithography"; Fritze et al.; Journal Vacuum. Sci Technology B; Vol. 19, No. 6, pp. 1366-2370; Nov/Dec 2001
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	AT	

Examiner Signature /Daborah Chacko-Davis/	Date Considered 11/14/2006
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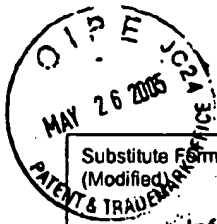
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DCD	AH	M. Fritze, et al., "Gratings of regular arrays and trim exposures for ultralarge scale integrated circuit phase-shift lithography", <i>J. of Vacuum Science & Technology B</i> , 19(6):2366-2370, Nov/Dec 2001.
DCD	AI	J.A. Hoffnagle, et al., "Liquid immersion deep-ultraviolet interferometric lithography", <i>J. of Vacuum Science & Technology B</i> , 17(6):3306-3309, Nov/Dec 1999.
DCD	AJ	Marc D. Levenson, et al., "Exposing the DUV SCAAM - 75 nm Imaging on the Cheap!", <i>Proc. of SPIE: Design, Process Integration, and Characterization for Microelectronics</i> , 4692:288-297, March 2002.
DCD	AK	Alex K. Raub, et al., "Deep UV immersion interferometric lithography", <i>Proc. of SPIE: Optical Microlithography XVI</i> , 5040:667-678, Feb. 2003.
DCD	AL	Bruce W. Smith, et al., "Water immersion optical lithography at 193 nm", <i>J. Microlith., Microfab., Microsyst.</i> , 3(1):44-51, Jan. 2004.
DCD	AM	Akiyoshi Susuki, et al., "Multilevel imaging system realizing $k_1 \approx 0.3$ lithography", <i>Proc. of SPIE: Optical Microlithography XII</i> , 3679:396-407, Mar. 1999.
DCD	AN	M. Switkes, et al., "Extending optics to 50 nm and beyond with immersion lithography", <i>J. of Vacuum Science & Technology B</i> , 21(6):2794-2799, Nov/Dec 2003.
DCD	AO	Brian Tyrrell, et al., "Investigation of the physical and practical limits of dense-only phase shift lithography for circuit feature definition", <i>J. Microlith., Microfab., Microsyst.</i> , 1(3):244-252, Oct. 2002.
DCD	AP	Saleem H. Zaidi, et al., "Multiple exposure interferometric lithography", <i>Proc. of SPIE: Optical Microlithography VII</i> , 2197:869-875, Mar. 1994.
DCD	AQ	M. Fritze, et al., "Preprint of poster presentation entitled "High-Throughput Hybrid Optical Maskless Lithography: All-Optical 32-nm Node Imaging," Presented at SPIE Microlithography 2005, San Jose, California, USA, March 3, 2005.

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(37 CFR §1.98(b))

Applicant
Yan BorodovskyFiling Date
October 17, 2003Group Art Unit
1765**U.S. Patent Documents**

Examiner Initial	Desig. ID	Document Number	Publication Date	Patentee	Class	Subclass	Filing Date If Appropriate
DCD	AA	2005/0073671	04/2005	Borodovsky			
DCD	AB	2005/0074698	04/2005	Borodovsky			
DCD	AC	2005/0083497	04/2005	Borodovsky			
DCD	AD	2005/0088633	04/2005	Borodovsky			
DCD	AE	5,759,744	06/1998	Brueck, et al.			
DCD	AF	6,042,998	03/2000	Brueck, et al.			
DCD	AG	6,233,044	05/2001	Brueck, et al.			
DCD	AH	6,548,820	04/2003	Mermelstein			
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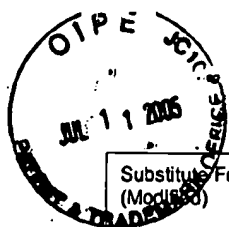
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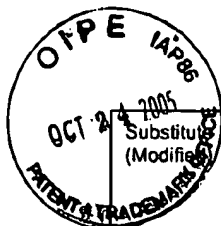
U.S. Patent Documents							
Examiner Initial	Desig. ID	Document Number	Publication Date	Patentee	Class	Subclass	Filing Date If Appropriate
DCD	AA	5,759,744	June 2, 1998	Brueck, et al.			
DCD	AB	5,415,835	May 16, 1995	Brueck, et al.			
DCD	AC	5,328,807	July 12, 1994	Tanaka, et al.			
DCD	AD	6,553,562	April 22, 2003	Capodieci, et al.			
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							Yes	No
DCD	AL	EP 0855623	July 29, 1998	EP				
DCD	AM	WO 98/32054	July 23, 1998	PCT				
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Other Documents (include Author, Title, Date, and Place of Publication)		
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DCD	AQ	Ishibashi, et al., "AFM Lithography Combined with Optical Lithography", <i>IEEE Microprocesses and Nanotechnology Conference 2000</i> , pp. 192-193 (July 2000).
DCD	AR	Martin, et al., "Ordered Magnetic Nanostructures: Fabrication and Properties", <i>J. Magnetism and Magnetic Materials</i> , 256(1-3):449-501 (January 2003).
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DCD	AA	2003/0091940	05/2003	Nakao			
DCD	AB	5,705,321	01/1998	Brueck, et al.			
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DCD	AM	0 915 384	05/1999	Europe				
DCD	AN	0 964 305	12/1999	Europe				
DCD	AO	2002-33265	01/2002	Japan (w/abstract)				X
DCD	AP	WO05/036273	04/2005	WIPO				
	AQ							

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DCD	AA	2004/0110092	06/2004	Lin			
DCD	AB	4,517,280	05/1985	Okamoto et al.			
DCD	AC	6,818,389	11/2004	Fritze et al.			
DCD	AD	6,884,551	04/2005	Fritze et al.			
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DCD	AO	WO97/48021	12/1997	WIPO				
DCD	AP	WO03/071587	08/2003	WIPO				
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DCD	AA	2002/0078427	06/2002	Palmer et al.			
DCD	AB	2005/0028129	02/2005	Hsu et al.			
DCD	AC	2006/0017910	01/2006	Borodovsky			
DCD	AD	5,041,361	08/1991	Tsuo			
DCD	AE	6,946,666	09/2005	Saito et al.			
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DCD	AL	WO 05/036274	04/2005	WIPO				
DCD	AM	WO 05/040920	05/2005	WIPO				
DCD	AN	WO 05/043249	05/2005	WIPO				
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